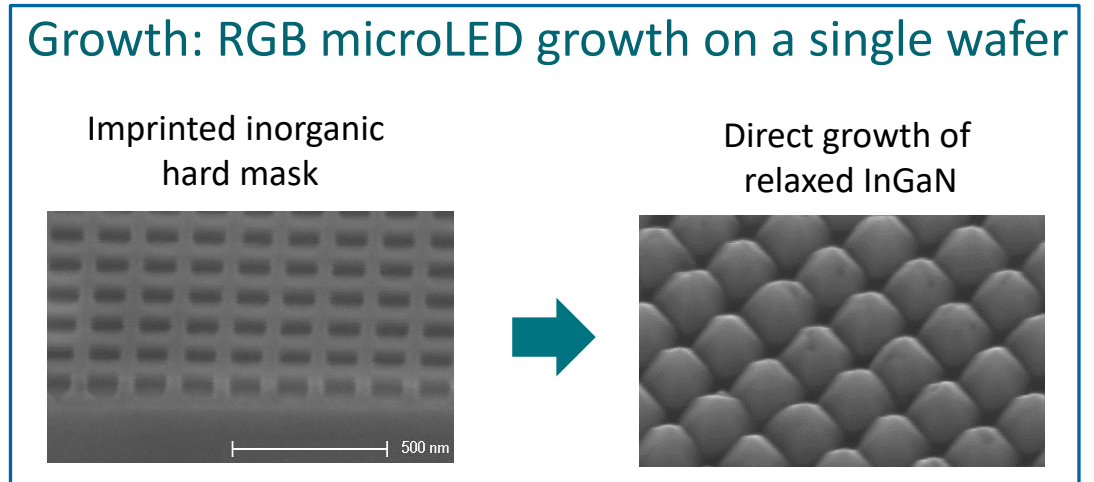


SCIL Nanoimprint solutions for wafer scale nano patterning



Secondary optics: Nano-photonics on microLED

~ 1 micron overlay accuracy on 300mm wafers

> 1.9 R.I inorganic imprint material

~1nm pattern variations

Meta lenses

DOE's

This block contains text describing secondary optics applications and two SEM images. The top image shows a grid of small circular features, labeled "Meta lenses". The bottom image shows a surface with a complex, repeating pattern of small, rounded structures, labeled "DOE's".

Wafer scale lithography

<100nm LED trench definition

Photonic crystals

Transparent /polarizer (contact)

Three SEM images are shown side-by-side. The left image shows a cross-section of a trench with a width of 97.8 nm and a depth of 60.3 nm. The middle image shows a top-down view of a regular array of circular holes, labeled "Photonic crystals". The right image shows a cross-section of a series of small, rounded structures on a surface, labeled "Transparent /polarizer (contact)".

Us to you: help you from proof of concept to pilot to HV

We like to see: your challenging use cases and demo capabilities